

Abstract

Susceptor for holding a semiconductor wafer with an orientation notch during the deposition of a layer on a front side of the semiconductor wafer and method for depositing the layer by using the susceptor

A susceptor for holding a semiconductor wafer with an orientation notch during the deposition of a layer on a front side of the semiconductor wafer and a method for depositing the layer by using the susceptor. The susceptor comprises a susceptor ring and a susceptor base, and the susceptor ring comprises a placement area for placing the semiconductor wafer in the edge region of a back side of the semiconductor wafer and a step-shaped outer delimitation of the susceptor ring adjoining the placement area. The susceptor has four positions at which the structure of the susceptor differs from the structure of the susceptor at four further positions, the spacing from one of the four positions to the next of the four positions being 90° and the spacing from one of the four positions to the next further position being 45° , and one of the four positions being a notch position, at which the structure of the susceptor differs from the structure of the susceptor at the three other positions of the four positions of the susceptor.

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Drawing for the abstract: Fig. 3